

The 23rd international conference on cyclotrons and their applications (**CYC** 2022)

Experimental study on proton irradiation effect of gallium nitride high electron mobility transistor

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December 5 2022•Beijing





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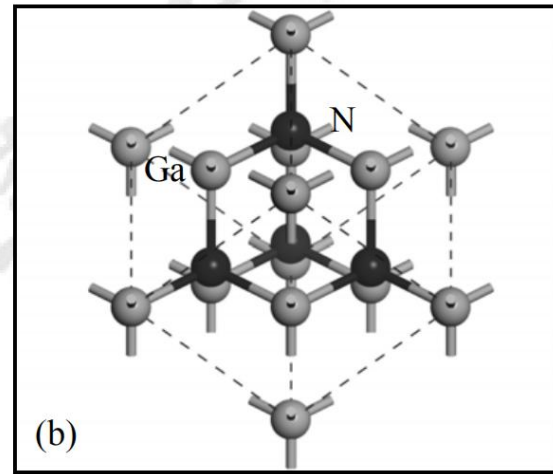
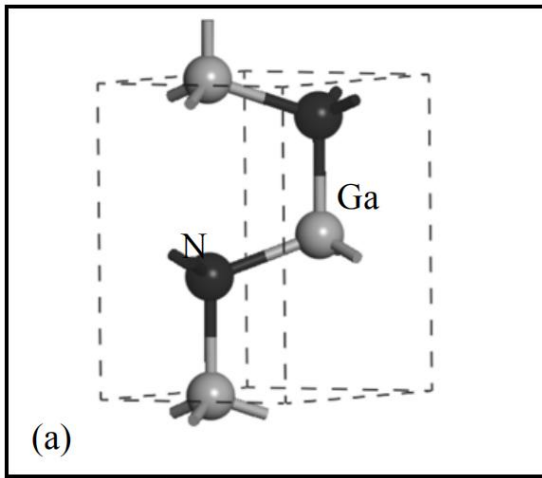
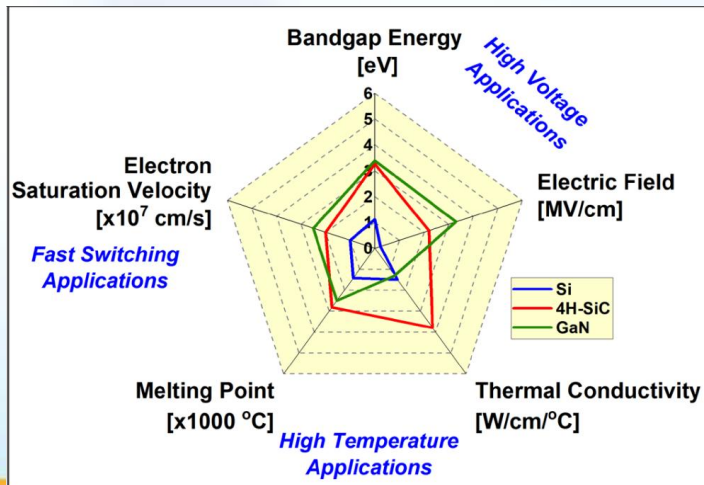
4 Conclusion



1. Background

Third generation semiconductor materials: Silicon carbide (SiC) and gallium nitride (GaN)

Excellent properties: High breakdown electric field, fast electron saturation speed, high working temperature, and excellent radiation resistance.



1. Background

In 1928, Johason et al. successfully synthesized GaN by hydride gas phase epitaxy (HVPE) technique.

In 1969, Maruska and Tietjen were the first to obtain GaN films on sapphire substrates using HVPE technology.

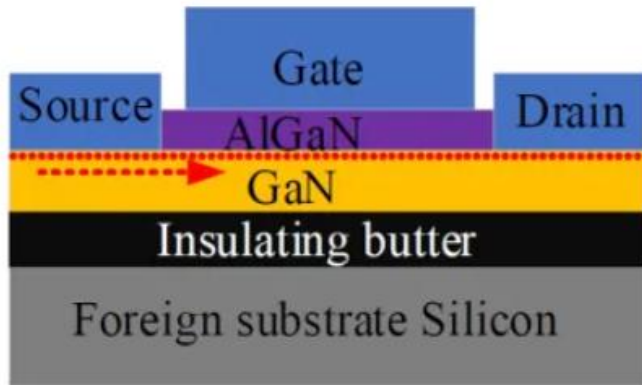
why is the GaN not widely used?

Until the 1990s, GaN has been developed rapidly due to the maturity of MOCVD technology.

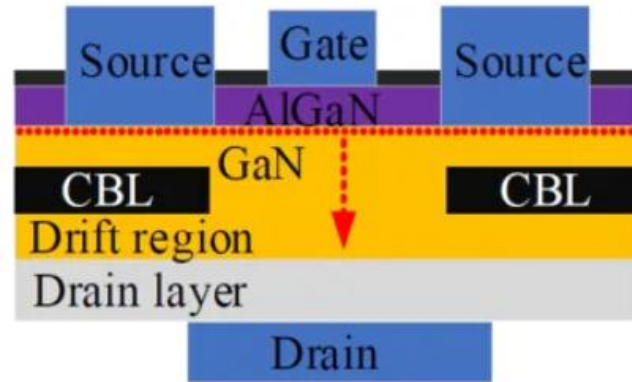
As an important member of GaN-based electronic devices, GaN high electron mobility transistor is widely considered by scientists to be used in the power supply and communication system of spacecraft and satellite.



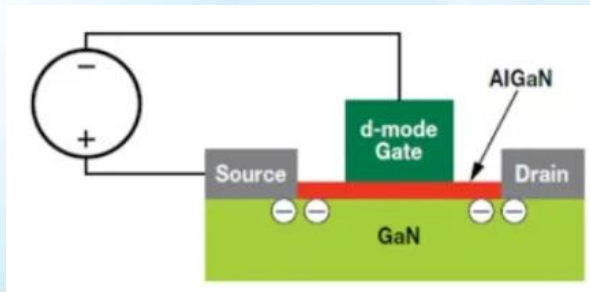
GaN HEMT structures



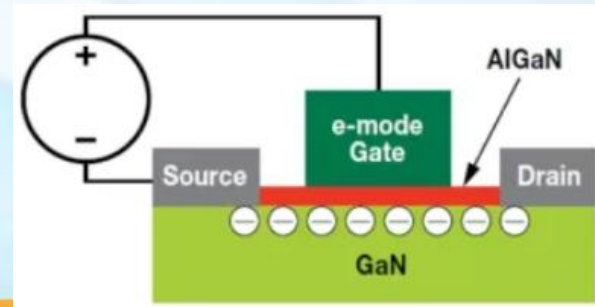
horizontal structure



vertical structure



normally-on



normally-off

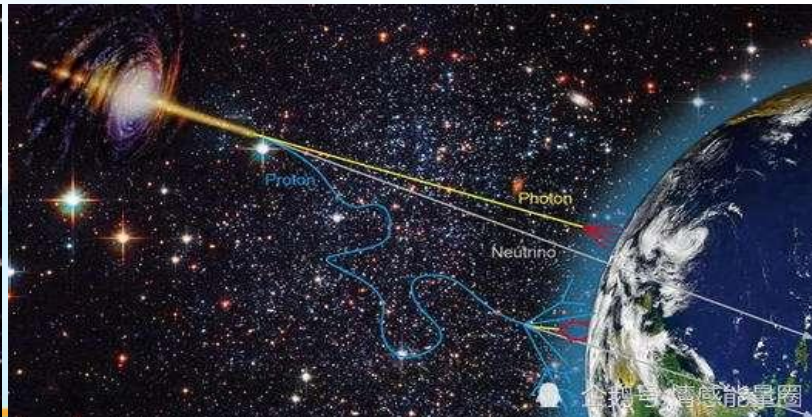
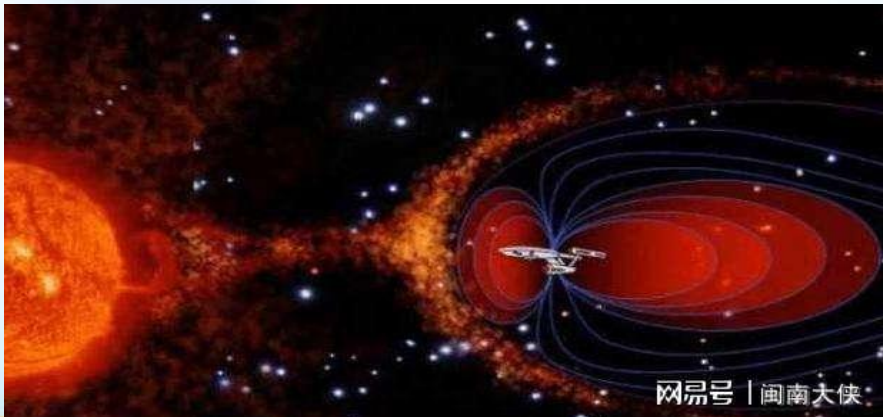
1. Background

GaN HEMTs will inevitably be affected by the space radiation environment during the space missions.

Solar cosmic rays: **Protons(mainly)**, electrons and heavy ions

Galactic cosmic rays: **Protons(85%)**, alpha ion(14%) and other heavy ions

Van•Allen belts: **Protons**, electrons and heavy ions



1. Background

The radiation effects of devices can be divided into **Single event effects (SEE)**, **Total ionizing dose effect (TID)** and **Displacement damage (DD)**.

Single event effects: The single energetic particle incident on the sensitive area of the electronic device results in the change of logic state, including SEU, SEB, SEL SEGR and so on.

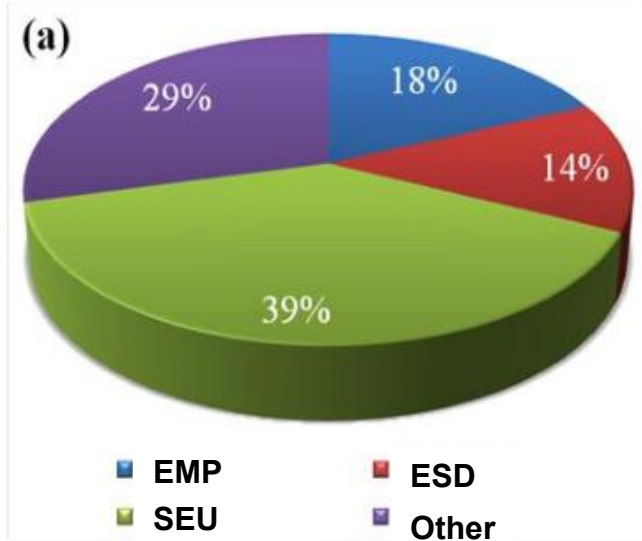
Total ionizing dose effect: The electrical parameters of electronic devices degrade with the increase of accumulated ionizing dose.

Displacement damage: High-energy particles irradiation causes atoms in semiconductor materials to leave their lattice positions

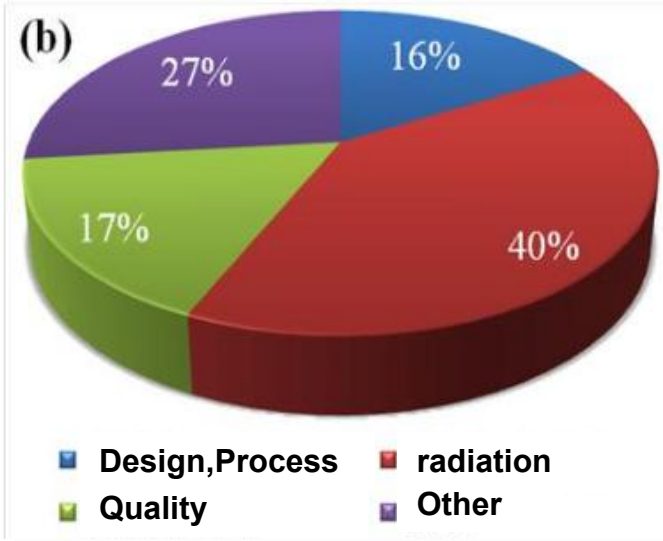


1. Background

According to statistics, from 1971 to 1986, a total of **1,589** failures occurred in **39** geostationary satellites, in which **1,129** failures were related to space radiation, and **621** of them were caused by the single event effect.



United States



China

1. Background

Due to the wide band gap of GaN, GaN-based electronic devices should have an excellent radiation resistance in theory.

Unfortunately, the radiation resistance of GaN HEMT is often affected by the preparation process and device structure, so the current radiation resistance of GaN HEMT is still not up to expectations.

The proton irradiation effect is very important for its future application in space

White et al. found that GaN HEMT performance did not change significantly when proton fluence is lower than 10^{14} p/cm², the degradation is enhanced with the increase of the proton fluence when the fluence was greater than 10^{15} p/cm².



1. Background

Kim et al. found that the performances degradation of GaN HEMT induced by low-energy proton irradiation was more serious than that of high-energy proton irradiation when the proton fluence is 10^{15} p/cm².

Greenlee et al. found that proton irradiation broadened the heterojunction interface in GaN HEMT, decreased the carrier density and mobility simultaneously.

Carey IV et al. found that increasing the content of Al in GaN HEMT could effectively weaken the effect of proton irradiation on its performance parameters.

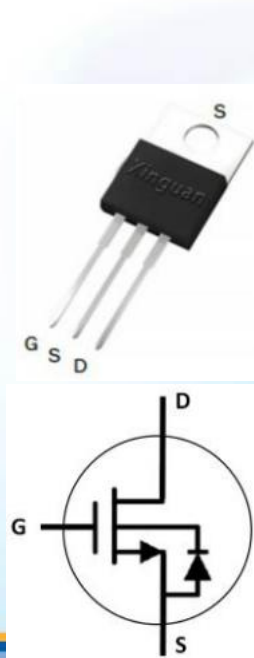
All the previous researches are based on proton irradiation experiments with energy less than 10 MeV.



2. Experimental details

The structure and electric parameters of the GaN HEMT are shown as below, produced by China Resources Microelectronics Limited (**CR MICRO**)

XG65T125PS1B



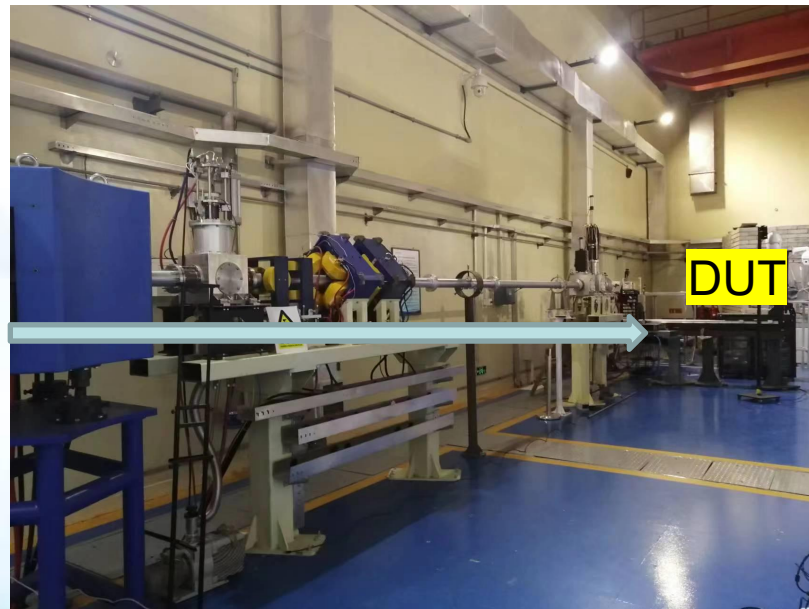
Parameter	Values	Test Condition
Drain source voltage	650V	$T_C=25^{\circ}\text{C}$
Continuous current	23A	$T_J = -55^{\circ}\text{C}$ to 150°C
Drain-source breakdown voltage	1700V	$V_{GS}=0\text{V}, I_{DSS}=250\mu\text{A}$
Gate threshold voltage	1.82	$V_{DS}=V_{GS}, I_D=500\mu\text{A}$
Drain-source leakage current	$8\mu\text{A}$	$V_{DS}=700\text{V}, V_{GS}=0\text{V}, T_J=25^{\circ}\text{C}$
Gate-source leakage current	150nA	$V_{GS}=20\text{V}$
Drain-source on-state resistance	$125\text{m}\Omega$	$V_{GS} = 6\text{ V}, I_D = 5\text{ A}$

2. Experimental details

The proton irradiation experiment of the GaN HEMT is carried out in the of China institute of atomic energy (CIAE).



CYCIAE-100 High current
Proton Cyclotron
Current: **200 μ A**

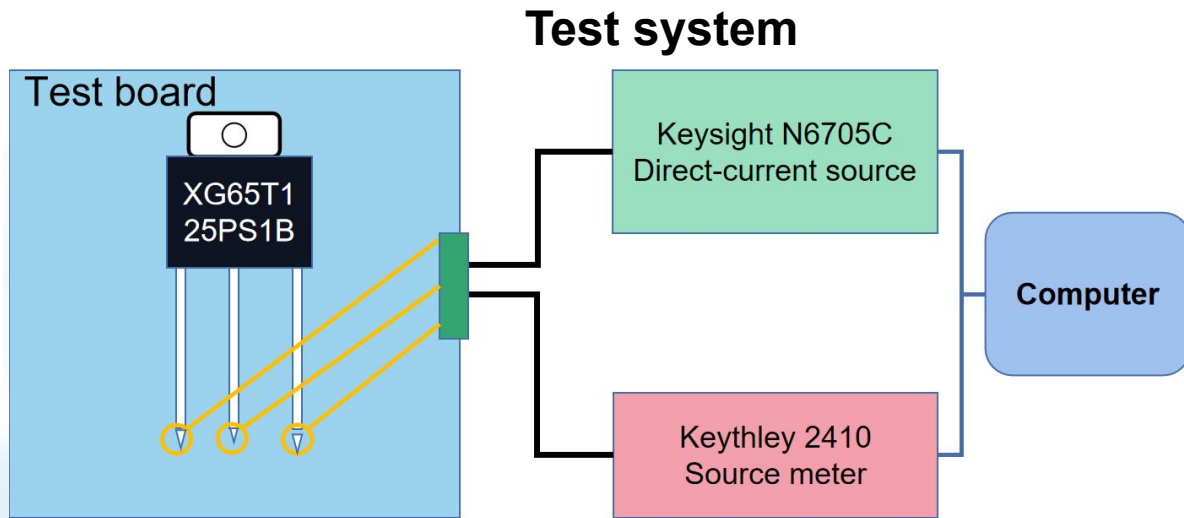


medium-energy proton irradiation platform
Energy range: **30-100MeV**
Fluence: **10^2 - 10^{11} p/cm²•s**

2. Experimental details

Proton irradiation

Parameter	Value
Energy	30,40,60,90MeV
fluence rate	10^8 p/cm ² •s
total fluence	10^{12} p/cm ²



The electrical parameters of GaN HEMT were measured at room temperature immediately after proton irradiation using the test system.

After annealing at room temperature for 10 days, the electrical parameters of the GaN HEMT were measured again by this system.



3. Results and Discussion

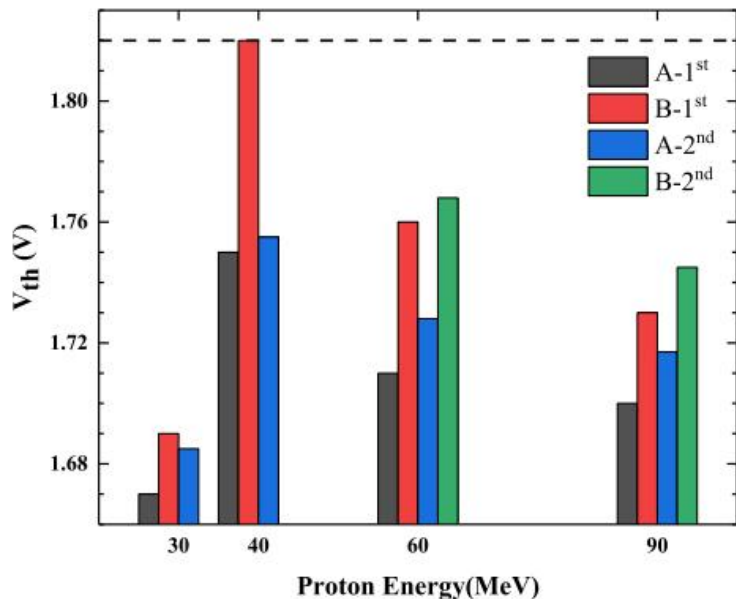


Fig.1 Gate-source threshold voltage of the GaN HEMT after proton irradiation with different energy

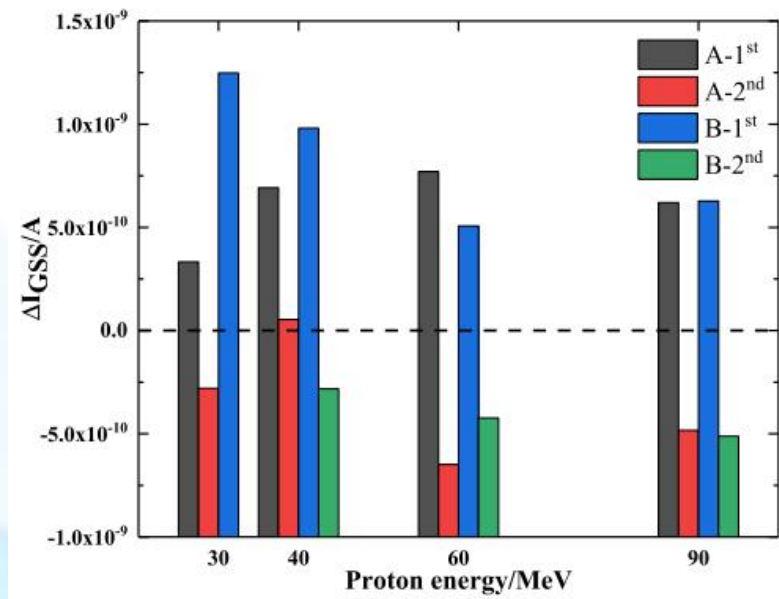


Fig.2 Static forward gate current of the GaN HEMT after proton irradiation with different energy.

3. Results and Discussion

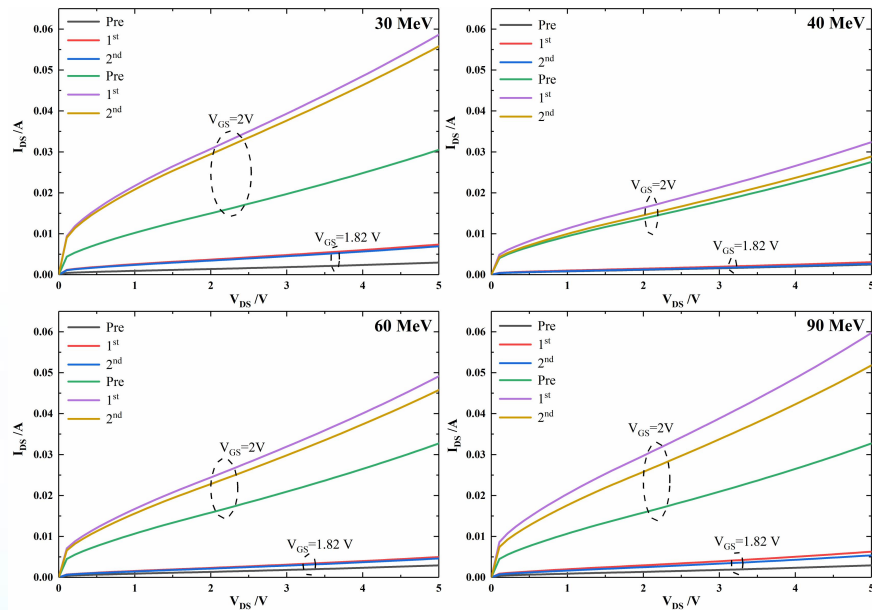


Fig.3 Output characteristic curves of the GaN HEMT in group A before and after proton irradiation with different energy

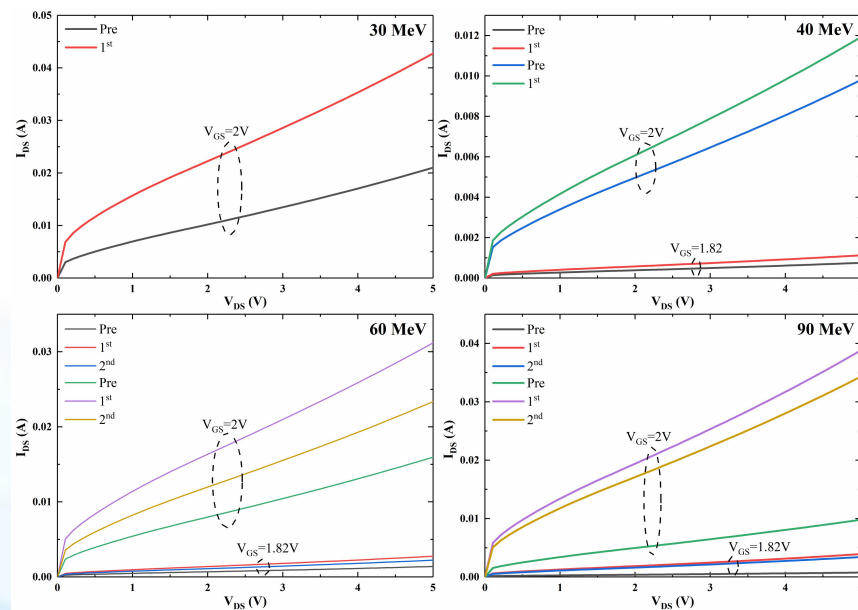


Fig.4 Output characteristic curves of the GaN HEMT in group B before and after proton irradiation with different energy

3. Results and Discussion

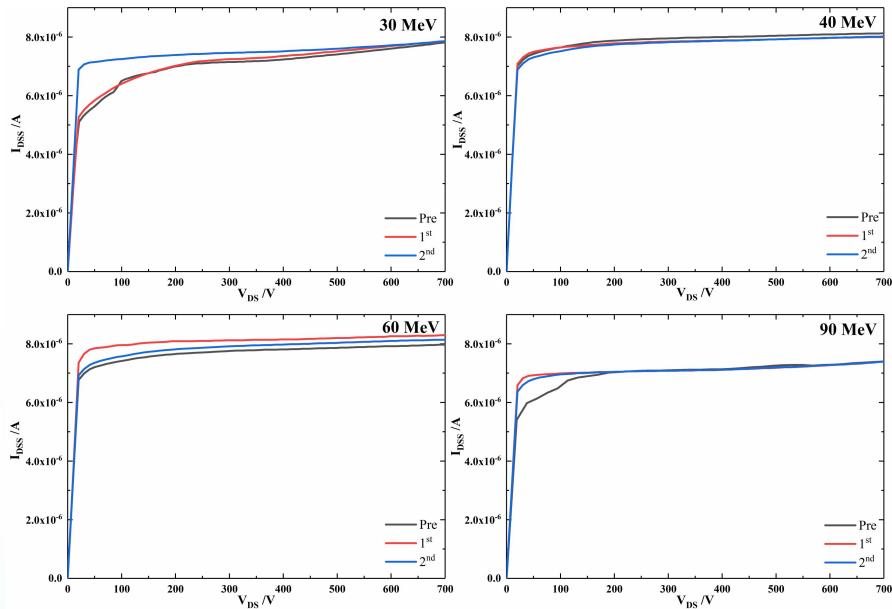


Fig.5 The off state leakage current of the GaN HEMT in group A before and after proton irradiation

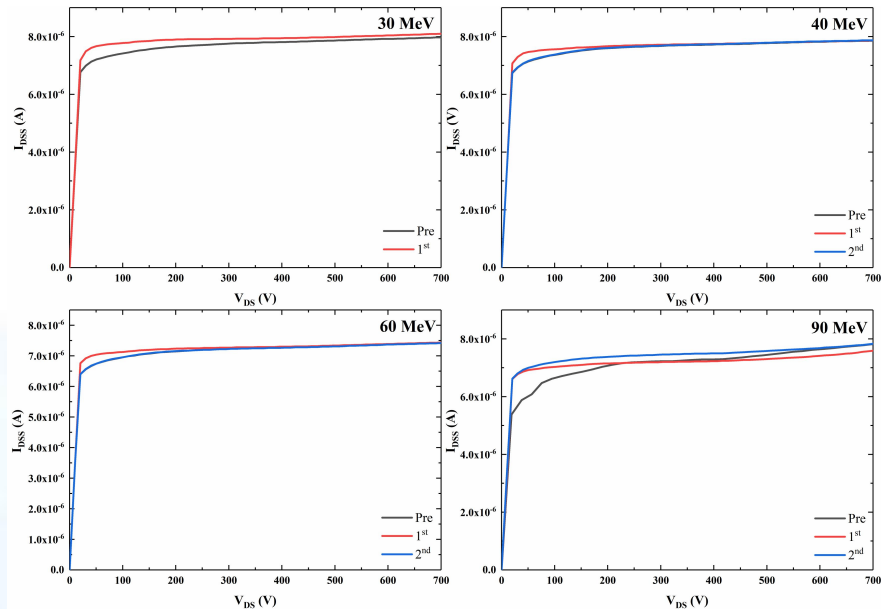


Fig.6 The off state leakage current of the GaN HEMT in group A before and after proton irradiation

3. Results and Discussion

- ① The gate-source threshold voltage of the GaN HEMT is decreased by proton irradiation, while the output characteristics, off-state leakage current and static forward gate current are increased by proton irradiation.
- ② After annealing at room temperature for 10 days, these electrical parameters of the GaN HEMT are restored to the corresponding values before proton irradiation.
- ③ The electrical properties of the GaN HEMT are improved after proton irradiation under the experimental conditions in this paper.





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Thank you!

CNNE

China National Nuclear Corporation

